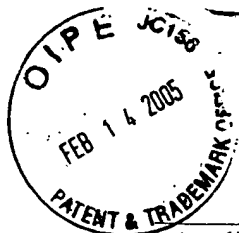




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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: STEGER

Examiner: UNKNOWN

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Title: METHODS AND APPARATUS FOR
IN SITU SUBSTRATE TEMPERATURE
MONITORING

INFORMATION DISCLOSURE STATEMENT

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